



MEXT (Ministry of Education, Culture, Sports, Science and Technology)
Program for Fostering Regional Innovation (Global Type)
-Tokai Region Nanotechnology Manufacturing Cluster-



Call for Papers

ISPlasma2013

5th International Symposium on
Advanced Plasma Science and its Applications for Nitrides and Nanomaterials

January 28 - February 1, 2013

Nagoya University, Japan

PLEASE NOTE!
Scheduled for January,
not March

Organizing Committee

Chairperson: Masaru Hori, Plasma Nanotechnology Research Center, Nagoya University
Vice-Chairperson: Hideki Masuda, Nagoya Institute of Technology
Keiji Nakamura, Chubu University
Mineo Hiramatsu, Meijo University

ISPlasma is specialized international symposium where more than 1,000 world-leading scientists and engineers can get together in the Tokai region (central Japan) to discuss latest researches in the fields of advanced plasma science, its application for processing and manufacturing of nitrides and nanomaterials, as well as new systems for technology transfers. This symposium will address issues such as global warming, resources and energy problems to which advanced plasma science and its application technologies can greatly contribute. We aim that holding this symposium series will establish an advanced plasma science and technology center in Tokai region which can collaborate with research institutes worldwide.

Plasma Science

- Plasma Source
- Modeling and Simulation
- Thin Film Deposition Process
- Plasma Biology and Medicine
- Plasma for Nanotechnology
- Advanced Plasma Measuring Technology
- Etching Process
- Flexible Electronics
- Plasma for Clean Energy

Nitride Semiconductors

- Crystal Growth of GaN and Related Materials
- Characterization
- Optical Devices
- MBE Growth of Nitrides
- Device Processing
- Electronic Devices

Nanomaterials

- Nanocarbon Materials
- Surface Modification/Surface Functionalization
- Nanoparticle/Nanowire/Nanorod
- Porous Materials
- Composite/Functionally Grade Materials
- Nanomaterials for Energy Applications

- ◆ Integration Technology of Plasma Science, Nitride Semiconductors and Nanomaterials
- ◆ Industry-Academia-Government Collaboration

● ABSTRACT SUBMISSION

Online abstract submission (one-page English) will be available from mid-June, 2012.

Deadline: September 18, 2012

● AWARD

Selected papers will be awarded.



<http://www.isplasma.jp/>

● SPECIAL ISSUE

Selected papers will be published in a special issue of Jpn. J. Appl. Phys. (JJAP). * tentative

Sponsored by

Aichi Science & Technology Foundation
ISPlasma2013 Organizing Committee

Contact: ISPlasma2013 Secretariat

c/o Aichi Science & Technology Foundation
E-mail: isplasma@astf.or.jp